

Abstract Submitted  
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**Electron transport in laterally confined phosphorus  $\delta$ -layers in silicon**<sup>1</sup> S.J. ROBINSON, J.R. TUCKER, University of Illinois at Urbana-Champaign, T.-C. SHEN, Utah State University — Carrier transport in 1D semiconductor structures has not been much studied experimentally because of the difficulty of confining dopant atoms in a quasi-1D configuration in a crystal. In the past few years we have developed a UHV-STM-based fabrication scheme to create 2D nanoscale patterns buried in crystalline silicon. By selectively desorbing H from a Si surface and dosing the dangling bonds with PH<sub>3</sub>, we can create laterally confined conductive P  $\delta$ -layers with widths on the order of 10 nm. These nanowires are connected to arrays of As-implanted contacts for transport characterization. Electrical measurements at cryogenic temperatures show ohmic behavior and magnetoconductance in accordance with weak localization theory. In addition, by lowering the temperature continuously, we find a clear 2D to 1D transition as the phase coherence length approaches the wire width. In 1D, the nanowire resistance becomes independent of temperature, indicating a saturation of the phase coherence and thermal lengths due to inelastic boundary scattering in the wire. Large-scale integration of  $\delta$ -layer devices and potential 3D architectures will become possible by employing the UHV-photolithography currently under development.

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